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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/801,190	03/15/2004	Lihua Li Huang	008670/DSM/LOW K	1633	
44257 7:	590 06/03/2005		EXAM	EXAMINER	
MOSER, PATTERSON & SHERIDAN, LLP APPLIED MATERIALS, INC.			LEE, GRANVILL D		
	K BOULEVARD, SUITE	E 1500	ART UNIT	PAPER NUMBER	
HOUSTON, T			2891	•	

DATE MAILED: 06/03/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

			H-7
	Application No.	Applicant(s)	
Office Action Summany	10/801,190	HUANG ET AL.	
Office Action Summary	Examiner	Art Unit	
	Granvill D. Lee Jr	2891	
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	correspondence address	
A SHORTENED STATUTORY PERIOD FOR REPL' THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1: after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period v - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	. 36(a). In no event, however, may a reply be tir y within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from , cause the application to become ABANDONE	nely filed rs will be considered timely. Ithe mailing date of this communication. CD (35 U.S.C. § 133).	
Status			
1) Responsive to communication(s) filed on <u>07 Fe</u>	ebruarv 2005.		
	action is non-final.	•	
3) Since this application is in condition for alloware closed in accordance with the practice under E	nce except for formal matters, pro		
Disposition of Claims			
4) ⊠ Claim(s) 1-20 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) ⊠ Claim(s) 1-19 is/are allowed. 6) ⊠ Claim(s) 20 is/are rejected. 7) □ Claim(s) is/are objected to. 8) □ Claim(s) are subject to restriction and/o	wn from consideration.		
Application Papers			
9) The specification is objected to by the Examine 10) The drawing(s) filed on 15 March 2004 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	a) accepted or b) objected t drawing(s) be held in abeyance. Se tion is required if the drawing(s) is ob	e 37 CFR 1.85(a). ejected to. See 37 CFR 1.121(d)	
Priority under 35 U.S.C. § 119		,	
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicat nty documents have been receiv u (PCT Rule 17.2(a)).	ion No ed in this National Stage	
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 6/21/2004.	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal R 6) Other:		

Application/Control Number: 10/801,190

Art Unit: 2891

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

The applied reference has a common assignee with the instant application. Based upon the earlier effective U.S. filing date of the reference, it constitutes prior art under 35 U.S.C. 102(e). This rejection under 35 U.S.C. 102(e) might be overcome either by a showing under 37 CFR 1.132 that any invention disclosed but not claimed in the reference was derived from the inventor of this application and is thus not the invention "by another," or by an appropriate showing under 37 CFR 1.131.

Claim 20 is rejected under 35 U.S.C. 102(e) as being anticipated by Xu et al. (US Pat. 6,656,837).

In view of this claim, Xu et al. discloses a method for processing a substrate, comprising, positioning the substrate in processing chamber

wherein the substrate has a barrier layer (Fig. 4c #512) comprising at least silicon and carbon (Col. 14 lines 54-60), introducing an organosilicon compound and an oxidizing gas into the chamber (Col. 6 lines 5-12) generating a plasma (Col. 2 lines 25-34) of the oxidizing gas (Col. 5 lines 17-27) and the organosilicon compound to form an initiation layer (#510) on the barrier layer. Xu et al. further introduces an organsilicon compound into chamber, which reacts with the oxidizing gas (Col. 5 lines 10-20) wherein the dielectric layer deposited comprises silicon, oxygen, and carbon and has a dielectric constant of about 3 or less (Col. 5 lines 29-35).

Allowable Subject Matter

Claims 1-19 are allowed.

Reasons for allowable subject matter, rest in the cited limitations of a first and second organsilicon compound to the oxidizing gas ratios. While Xu et al. appears to teach a range (1:1 to 100:1) for the organsilicon to oxidizing gas ratio, no stated ratios are present in the individual layer steps, and in fact, the examples provide by Xu et al. fails to teach within the stated range they suggest, and therefore away from the claimed invention.

Contact Information

Any inquiry concerning this communication or earlier communications for the examiner should be directed to Granvill Lee

whose telephone number is (571) 272-1897. The examiner can be normally reached on Monday thru Friday from 8:00 am to 4:30 pm.

If attempts to reach the examiner by telephone are not successful, the examiner's supervisor, Bill Baumeister can be reached on (571) 272-1722. The fax phone number for this group is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Examiner Granvill Lee Art Unit 2891

Gl 5/11/05

> B. WILLIAM BAUMEISTER SUPERVISORY PATENT EXAMINER